

Fig. 1

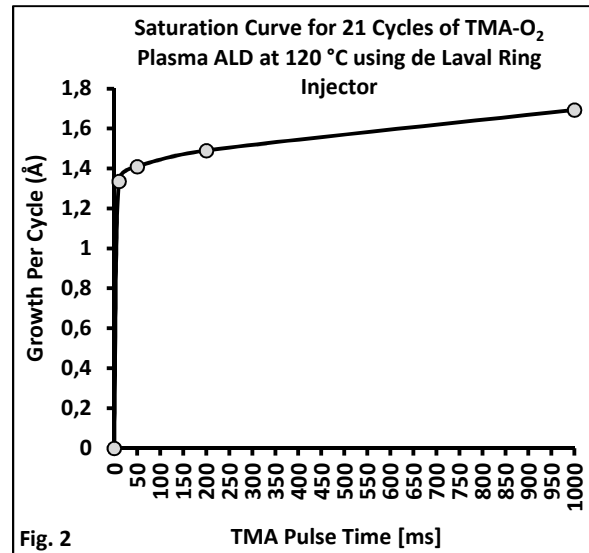


Fig. 2

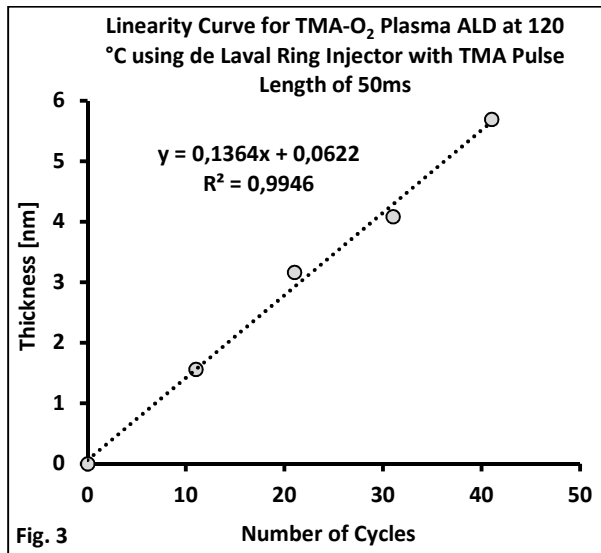


Fig. 3

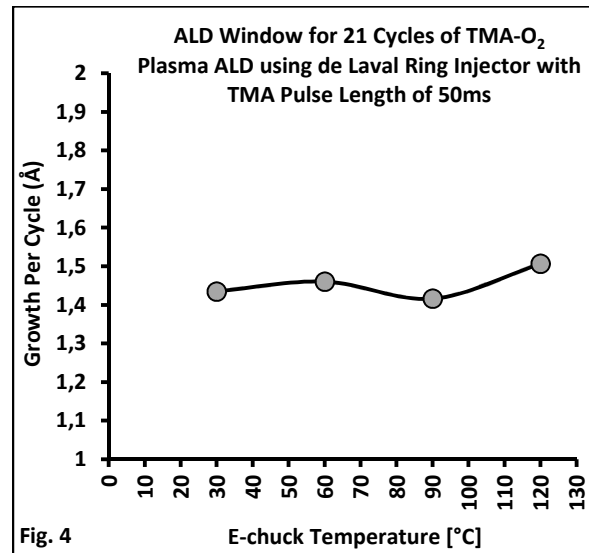


Fig. 4

Table 1. Angle Resolved XPS Analysis			Relative Stoichiometry [%]				
			Surface	Al <sub>2</sub> O <sub>3</sub> ALD film		SiO <sub>2</sub> interface	Bulk Si
Configuration	TMA Pulse [ms]	Wafer Temp. [°C]	C 1s	O 1s	Al 2p	SiO <sub>2</sub> (Fit)	Si (Fit)
Single capillary injector	1000	30	100	47,8	52,2	100	100
de Laval Ring injector	50	120	100	73,1	26,9	100	100
de Laval Ring injector	10	120	100	73,8	26,2	100	100